

## 5

### 5.17

A Si  $p^+-n$  junction has a donor doping of  $5 \times 10^{16} \text{ cm}^{-3}$  on the  $n$  side and a cross-sectional area of  $10^{-3} \text{ cm}^2$ . If  $\tau_p = 1 \text{ } \mu\text{s}$  and  $D_p = 10 \text{ cm}^2/\text{s}$ , calculate the current with a forward bias of  $0.5 \text{ V}$  at  $300 \text{ K}$ .

✓ Answer ✓

$$p_n = \frac{n_i^2}{N_d}$$

$$L_p = \sqrt{\tau_p D_p}$$

$$I_p = qA \frac{D_p}{L_p} p_n (e^{qV/kT} - 1)$$

$$I_p = qA \frac{D_p}{\sqrt{\tau_p D_p}} \frac{n_i^2}{N_d} (e^{qV/kT} - 1)$$

$$I_p = qA \frac{D_p}{\sqrt{\tau_p D_p}} \frac{n_i^2}{N_d} (e^{qV/kT} - 1)$$

$$I \approx I_p = 5.513 \times 10^{-7} \text{ A}$$

### 5.19

a

A Si  $p^+-n$  junction  $10^{-2} \text{ cm}^2$  in area has  $N_d = 10^{15} \text{ cm}^{-3}$  doping on the  $n$  side. Calculate the junction capacitance with a reverse bias of  $10 \text{ V}$ .

✓ Answer

$$C_j = \frac{\epsilon_r \epsilon_0 A}{W}$$

$$W = \sqrt{\frac{2\epsilon(V_0 - V)}{q} \left( \frac{N_a + N_d}{N_a N_d} \right)} \approx \sqrt{\frac{2\epsilon V_r}{q} \left( \frac{1}{N_d} \right)}$$

$$C_j = A \sqrt{\frac{q\epsilon_r \epsilon_0 N_d}{2V_r}}$$

$$C_j = 2.890 \times 10^{-11} \text{ F}$$

b

An abrupt  $p^+-n$  junction is formed in Si with a donor doping of  $N_d = 10^{15} \text{ cm}^{-3}$ . What is the depletion region thickness  $W$  just prior to avalanche breakdown?

✓ Answer

I could not find the formula for anything related to avalanche breakdown on the slides or in the text, but the  $W$  region should increase in size, but with a strong enough field that a multiplicative effect is realized in electrons with EHPs.

## 5.24

A Si  $p$ - $n$  junction with cross-sectional area  $A = 0.001 \text{ cm}^2$  is formed with  $N_a = 10^{15} \text{ cm}^{-3}$  and  $N_d = 10^{20} \text{ cm}^{-3}$ .

Calculate:

**a**

Contact potential  $V_0$ .

✓ **Answer**

$$V_0 = \frac{kT}{q} \ln \left( \frac{N_a N_d}{n_i^2} \right)$$

$$V_0 = 0.8735512160281839 \text{ V}$$

**b**

Space-charge width at equilibrium (zero bias).

✓ **Answer**

$$W = \sqrt{\frac{2\epsilon(V_0 - V)}{q} \left( \frac{N_a + N_d}{N_a N_d} \right)}$$

$$W = 1.067859223747202 \text{ } \mu\text{m}$$

**c**

Current with a forward bias of  $0.7 \text{ V}$ . Assume  $\mu_n = 1500 \text{ cm}^2/\text{Vs}$ ,  $\mu_p = 450 \text{ cm}^2/\text{Vs}$ , and  $\tau_n = \tau_p = 2.5 \text{ ns}$ . Which carries most of the current, electrons or holes, and why? If you wanted to double the electron current, what should you do?

✓ **Answer**

$$I_p = qA \frac{D_p}{L_p} p_n (e^{qV/kT} - 1)$$

$$I_n = qA \frac{D_n}{L_n} n_p (e^{qV/kT} - 1)$$

$$L = \sqrt{D\tau}$$

$$\frac{kT}{q} = \frac{D}{\mu}$$

$$p_n = \frac{n_i^2}{N_d}$$

$$n_p = \frac{n_i^2}{N_a}$$

$$I_p = qA \sqrt{\frac{kT\mu_p}{q\tau_p} \frac{n_i^2}{N_d}} (e^{qV/kT} - 1)$$

$$I_n = qA \sqrt{\frac{kT\mu_n}{q\tau_n} \frac{n_i^2}{N_d}} (e^{qV/kT} - 1)$$

$$I_p = 1.344 \times 10^{-8} \text{ A}$$

$$I_n = 0.002453 \text{ A}$$

$I_p > I_n$  therefore the holes carry more current.

$$I = I_n = 2.453 \text{ mA}$$

I would decrease  $N_d$

## 5.45

A Schottky barrier is formed between a metal having a work function of  $4.3 \text{ eV}$  and p-type Si (electron affinity =  $4 \text{ eV}$ ). The acceptor doping in the Si is  $10^{17} \text{ cm}^{-3}$ .

**a**

Draw the equilibrium band diagram, showing a numerical value for  $qV_0$ .

✓ **Answer**

$$\phi_M = 4.3 \text{ eV}$$

$$\chi_{Si} = 4 \text{ eV}$$

$$N_a = 10^{17} \text{ cm}^{-3}$$

$$p_0 = n_i e^{(E_i - E_F)/kT}$$

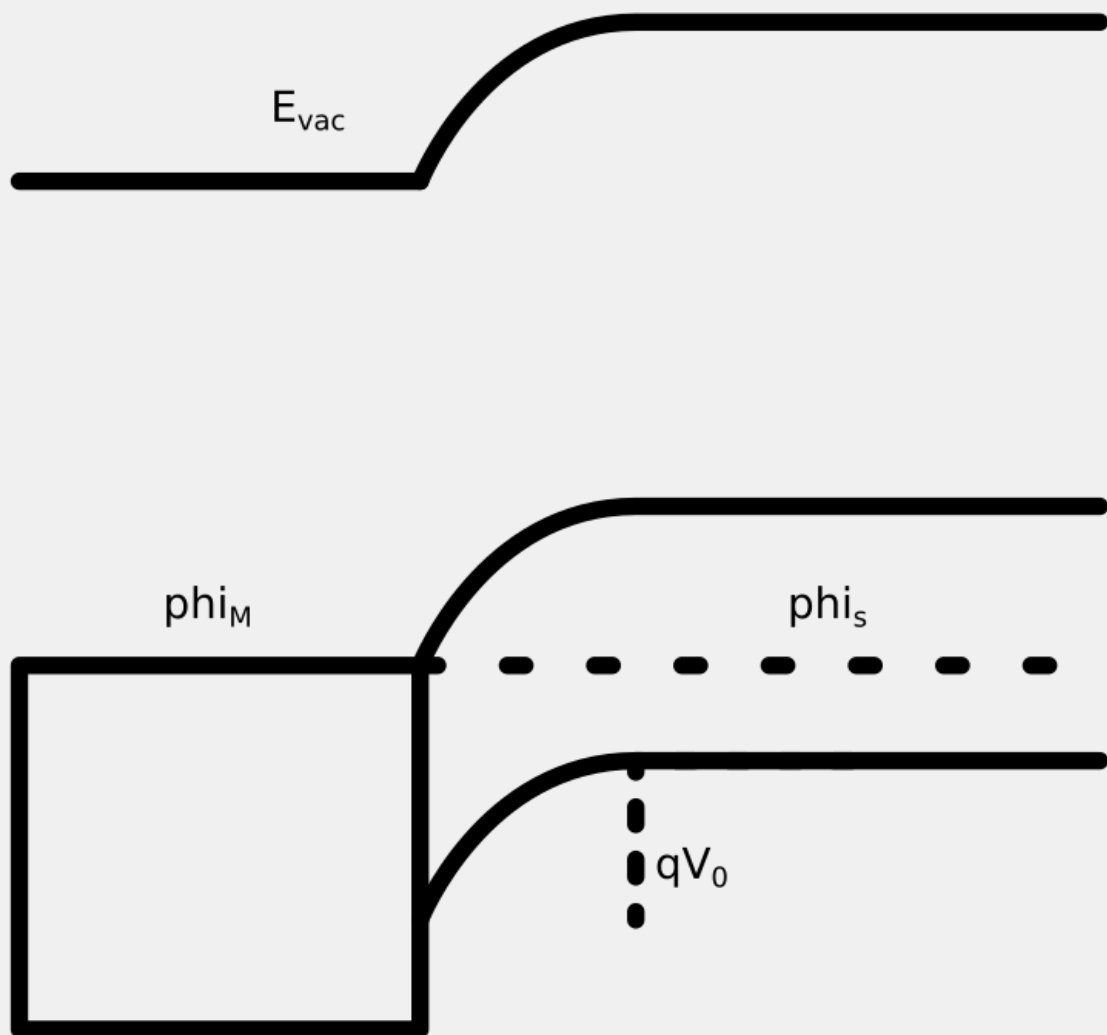
$$E_i - E_F = kT \ln \left( \frac{p_0}{n_i} \right)$$

$$E_i - E_F = 0.406957131059819 \text{ eV}$$

$$\phi_s = E_g + \chi_{Si} + E_F - E_V = 4.71 \text{ eV}$$

$$\phi_s > \phi_M$$

$$V_0 = \phi_s - \phi_M = 0.41 \text{ eV}$$



**b**

Draw the band diagram with  $0.3\text{ V}$  forward bias. Repeat for  $2\text{ V}$  reverse bias.

✓ **Answer**

The barrier height would change depending on the bias

With a  $0.3\text{ V}$  forward, we would have  $qV_0 = 0.11\text{ eV}$

With a  $2\text{ V}$  reverse, we would have  $qV_0 = 2.41\text{ eV}$